

Serial No. 09/771,651

WATZENBERGER et al.

PF 0000051146

## A P P E N D I X I:

THE LISTING OF CLAIMS (version with markings):

1. (previously presented) A process for working up a solution of hydroxylamine and amines, which comprises passing the solution into a rectification column, and stripping the hydroxylamine from the solution by the countercurrent method with steam to obtain a top product comprising aqueous hydroxylamine and a bottom product comprising amines.
2. (canceled)
3. (canceled)
4. (previously presented) A process as claimed in claim 1, wherein the rectification column is operated at from 0.1 to 1.0 atmosphere.
5. (previously presented) A process as claimed in claim 1, wherein a fraction of the bottom product is vaporized by means of an evaporator and the vaporized fraction is recycled to the rectification column.
6. (previously presented) A process as claimed in claim 1, wherein water is added to the rectification column.
7. (previously presented) A process as claimed in claim 4, wherein the rectification column is operated at from 0.8 to 1.0 atmosphere.
8. (previously presented) A process as claimed in claim 6, wherein the water is passed into the bottom of the rectification column.
9. (previously presented) A process as claimed in claim 1, wherein the solution is a solution used for cleaning electronic components.
10. (previously presented) A process for working up a solution of hydroxylamine and amines,  
wherein the hydroxylamine is stripped from the solution with steam,  
wherein the solution is passed into a rectification column and steam is passed counter-currently through the column, whereby a top product comprising aqueous hydroxylamine and a bottom product comprising amines are obtained, and  
wherein the top product is condensed and is partly recycled to the rectification column with a reflux ratio of less than 0.5.

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11. (previously presented) A process as claimed in claim 10, wherein the rectification column is operated at from 0.1 to 1.0 atmosphere.
12. (previously presented) A process as claimed in claim 11, wherein the rectification column is operated at from 0.8 to 1.0 atmosphere.
13. (previously presented) A process as claimed in claim 10, wherein a fraction of the bottom product is vaporized by means of an evaporator and the vaporized fraction is recycled to the rectification column.
14. (previously presented) A process as claimed in claim 10, wherein water is added to the rectification column.
15. (previously presented) A process as claimed in claim 14, wherein the water is passed into the bottom of the rectification column.
16. (previously presented) A process as claimed in claim 10, wherein the solution is a solution used for cleaning electronic components.
17. (new) A process as claimed in claim 1, wherein the solution of hydroxylamine and amines comprises a bacteriotoxic amine.
18. (new) A process as claimed in claim 1, wherein the solution of hydroxylamine and amines comprises N-methylpyrrolidone.
19. (new) A process as claimed in claim 10, wherein the solution of hydroxylamine and amines comprises a bacteriotoxic amine.
20. (new) A process as claimed in claim 10, wherein the solution of hydroxylamine and amines comprises N-methylpyrrolidone.